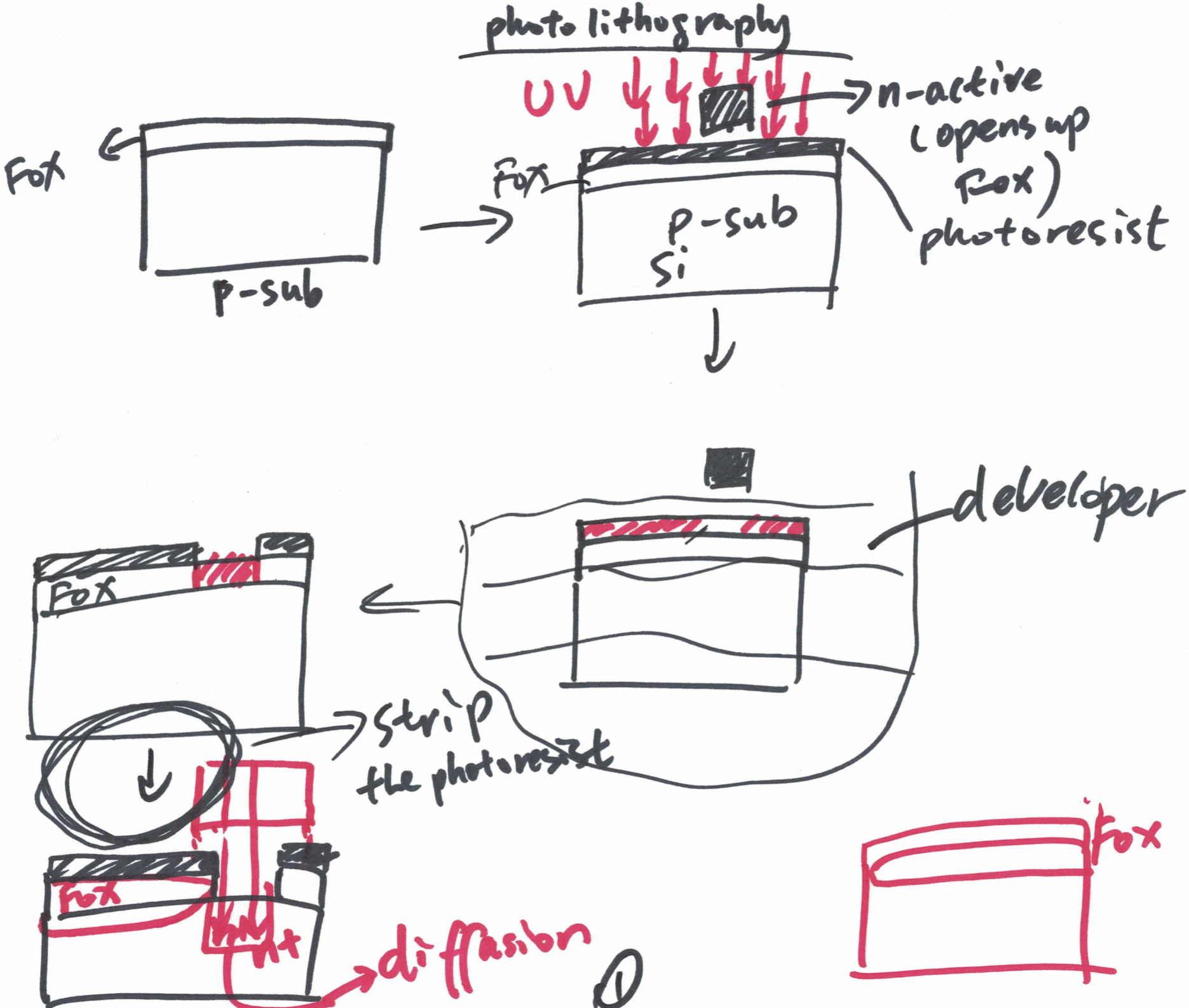

photolithography
UV
n-active
(opens up
Fox)
photoresist
Fox
p-sub
Si
Fox
p-sub
developer
Fox
strip
the photoresist
Fox
n+
diffusion
Fox

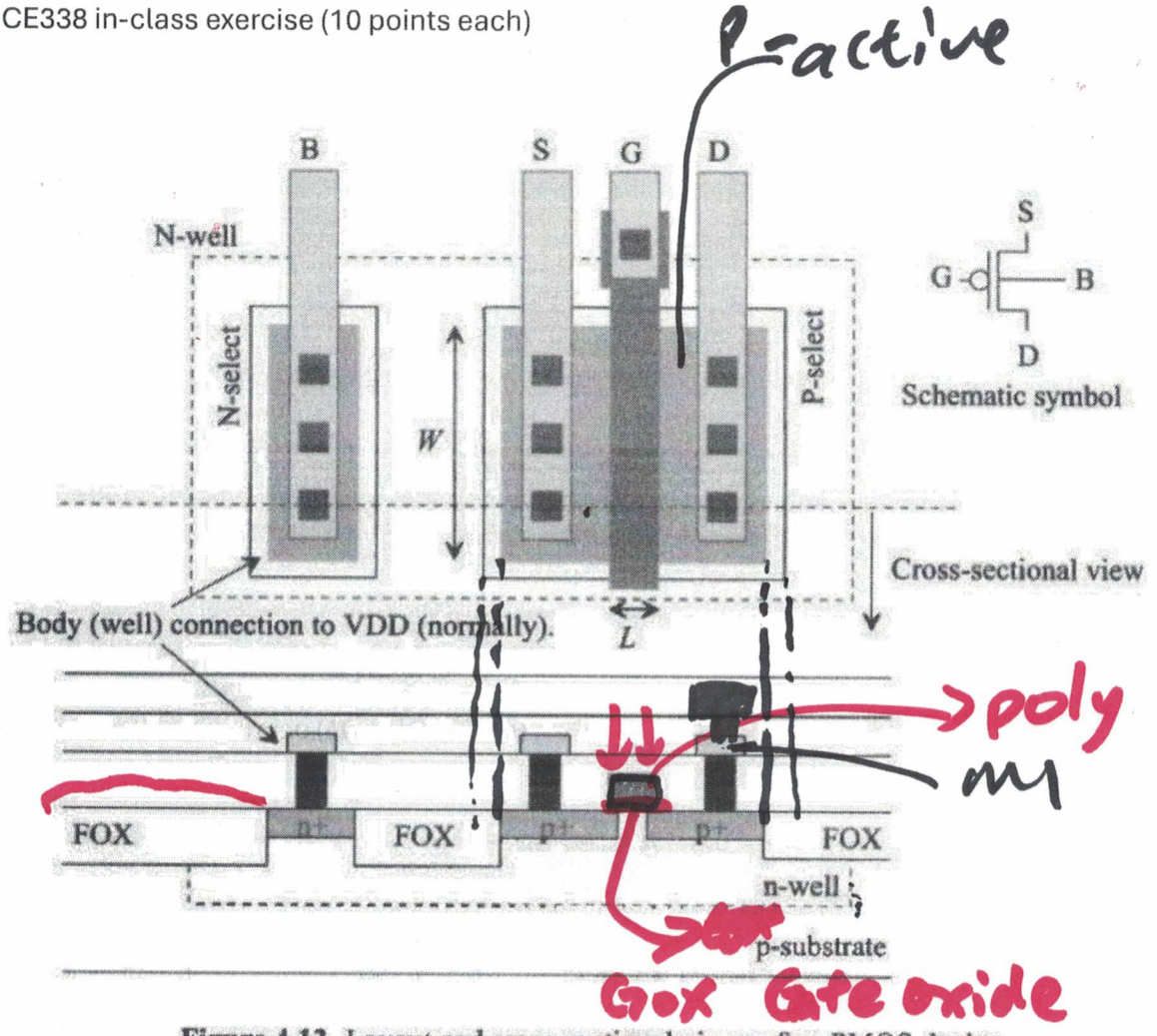


Figure 4.13 Layout and cross-sectional views of an PMOS device.

bottom-up

CE338 in-class exercise (10 points each)

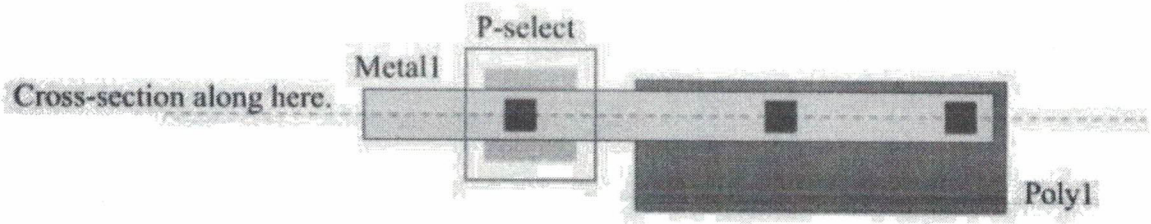


Figure 4.22 Layout used in Problem 4.10.

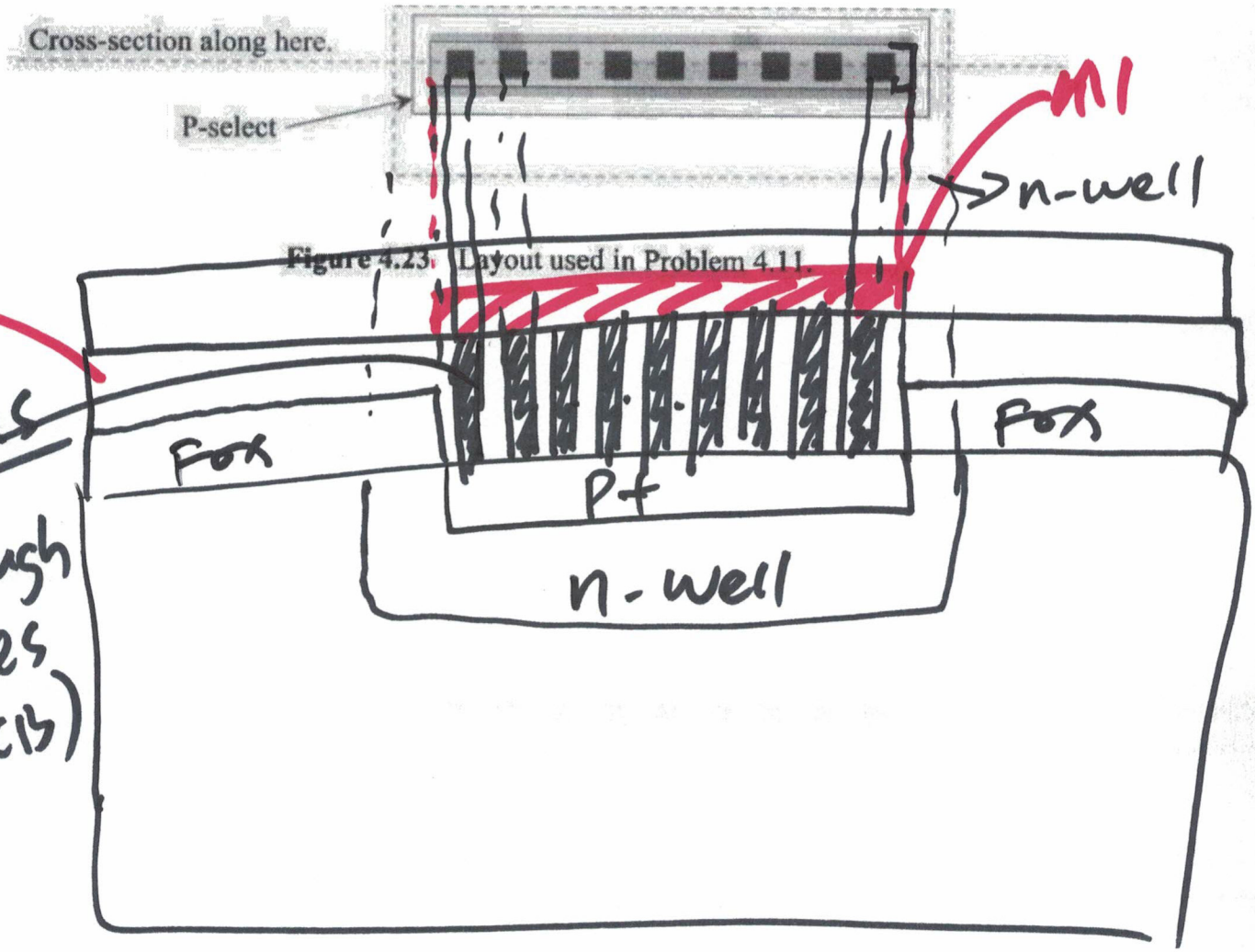
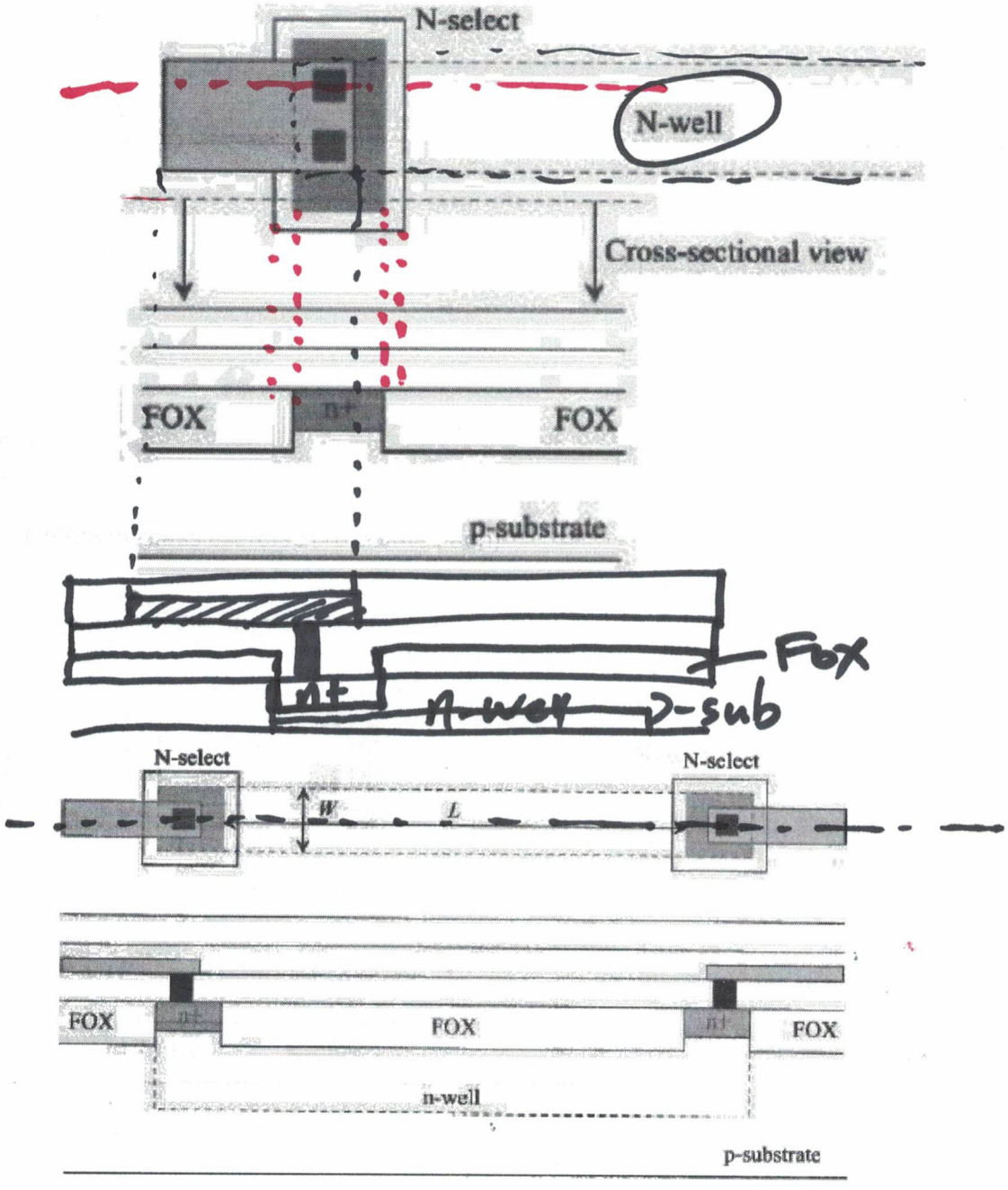
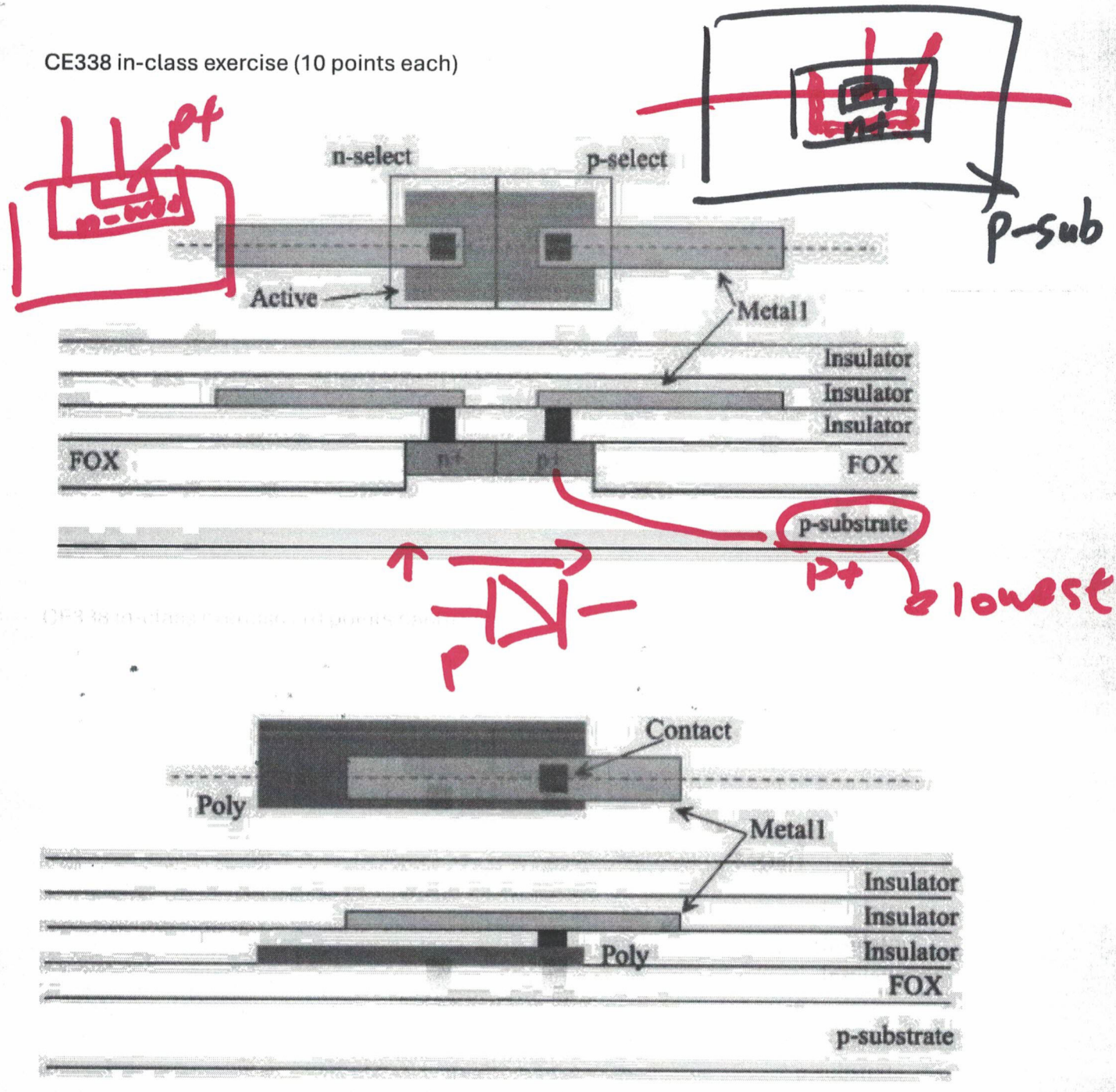


Figure 4.23 Layout used in Problem 4.11.

CE338 in-class exercise (10 points each)



CE338 in-class exercise (10 points each)